Fusion 200 ACU Technical information

Use:	Photoresist stripping at atmospheric pressure
Features:	 High ashing rates allowing high system throughput Low particulates with minimum residues Endpoint detection or timed ashing process control Independent gas flow control through 2 mass flow controllers Maximum 3 step process to 999 second total cycle time Capacity for storage of up to 26 processes in non-volatile memory Resistance heated vacuum wafer chuck Ozonizer produces > 8% by weight of O₃ at 24 slm with pure O₂ gas feed Temperature control via thermocouple sensor imbedded in wafer chuck Typical range of operation: 200° - 350° C Two arm, high precision, three dimensional robot compatible with uni-cassette Compatible with any "H" bar cassette Process, maintenance and diagnostic screens
Dimensions:	• 35" W X 51" D X 70" H; 1,600 pounds
Electrical:	All standard voltages; 50 or 60 MHz; 3 phase; 7.0 KVA connected power
Compressed Air:	12 scfm at 70 psi
Cooling Water:	0.35 gpm at 20 psi; must be > 1.0 X 106 ohm-cm resistivity
Oxygen:	• 25 slm @ 45 psi
Nitrous Oxide:	• 1 slm @ 45 psi
Ozonizer Chiller:	208 - 240 VAC; 50/60 Hz; Single phase; 15 amp
Vacuum:	20" Hg or greater
Drain:	Low back pressure, vented gravity drain; suitable for service to 250° F